

**JRF (or SRF) advertisement in the School of Material Science and Technology,  
IIT(BHU), Varanasi-221005**

**Project reference no: R&D/SERB/LT/SMST/16-17/07**

Applications are invited for aJRF (or SRF) position in SERB Sponsored Project under the project title “Development of low-voltage, low-power, colloidal quantum dot light-emitting transistors for next generation display technology”. The post is purely temporary and co-terminus with the project. JRF (or SRF) @ Rs. 25,000/- PM fixed (or 28,000/- PM) +20% HRA up to completion of project.

(Who applied before for this position is not required to apply again)

**Essential Qualifications:**

**SRF:** Age: Upper Age limit – 32 years: (5 years' relaxation for Female/SC/ST/ Physically Handicapped Candidate) or as per specifications of the funding agency concerned. Qualification/Experience: NET/GATE or equivalent as per specifications of the funding Agency concerned with 55% marks (equivalent grade) in Post-Graduation/qualifying degree. At least two years' research experience in related field.

**JRF:** Age: Upper age limit – 28 years: (5 years' relaxation for Female/SC/ST/ Physically Handicapped Candidate) or as per specifications of the funding agency concerned. Qualification: NET/GATE or equivalent as per specifications of the funding agency concerned with 55% marks (equivalent grade) in Post-Graduation/qualifying degree.

**Desirable Qualifications: Experience in thin film device fabrication and characterization is preferred.**

Applications on Plain paper giving Name, Photograph, Permanent and Corresponding address, Name of Father and Mother, Telephone no. and e-mail address, details of educational career (starting from High School or equivalent) along with self-attested copies of all mark-sheets & certificates and details of any research or other experiences etc. should reach within 21 days to **Dr. BholaNath Pal (P.I.)**, School of Materials Science and Technology, Indian Institute of Technology (BHU), Varanasi-221005. No TA/DA will be paid if called for interview.